







## Spin *Lift-off*

Power your performance today and tomorrow with our advanced metal lift-off process tool!

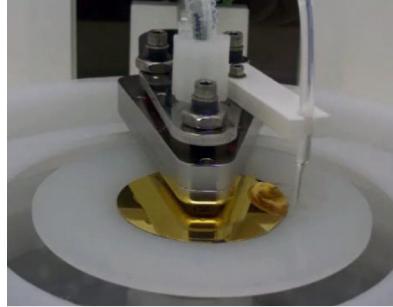


## **BENEFITS**

- > Uncritical chemicals (replacing e.g. Aceton, ISO, NMP)
- > Low chemical consumption
- > Cost reduction for our customers
- > Intelligent filter systems
- > Enhancement of process capability

- > High safety levels for chemicals
- > State of the art software with multi-touch functions
- > Easy to configure and upgradeable
- > Optimized footprint





## **APPLICATIONS**

The **Spin** *Lift-off* is designed for processes like:

- > Metal lift-off
- > Photoresist strip

## **OPTIONS**

- > Semi or fully automated
- > Unique pre-soak system
- > DI-water high pressure cleaning
- > IPA rinse
- > SECS GEM interface

TECHNICAL DATA	Spin Lift-off 200-S	Spin <i>Lift-off</i> 200-F
Automation	Semi automated	Fully automated
Wafer size	up to 200 mm	up to 200 mm
Pre-soak	no	yes
Backside protection	yes	yes
Upgrade in the field	yes	yes
Dimensions (W x D x H)	600 x 1300 x 2000 mm	1600 x 1300 x 2000 mm